



Attorney's Docket No. 5308-157IP2

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Das et al.

Serial No.: 10/045,542

Filed: October 26, 2001

For: METHOD OF FABRICATING AN OXIDE LAYER ON A SILICON  
CARBIDE LAYER UTILIZING AN ANNEAL IN A HYDROGEN  
ENVIRONMENT

Confirmation No.: 3570

Group Art Unit: 1762

Examiner: Michael. E. Barr

Mail Stop Non-Fee Amendment  
Commissioner for Patents  
Washington, DC 20231

AMENDMENT

Sir:

Applicants respectfully request entry of the following amendment in the  
above-referenced application.

**Amendments to the Specification** begin on page 2 of this paper.